

(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property
Organization
International Bureau

(43) International Publication Date
05 May 2022 (05.05.2022)



(10) International Publication Number
WO 2022/093546 A1

(51) International Patent Classification:

H01L 21/764 (2006.01) *H01L 21/3105* (2006.01)
H01L 21/67 (2006.01) *C23C 16/04* (2006.01)
H01L 21/02 (2006.01) *C23C 16/26* (2006.01)
H01L 21/768 (2006.01) *C23C 16/505* (2006.01)
H01L 21/311 (2006.01)

(21) International Application Number:

PCT/US2021/055125

(22) International Filing Date:

15 October 2021 (15.10.2021)

(25) Filing Language:

English

(26) Publication Language:

English

(30) Priority Data:

17/079,630 26 October 2020 (26.10.2020) US

(71) Applicant: **APPLIED MATERIALS, INC.** [US/US];
3050 Bowers Avenue, Santa Clara, California 95054 (US).

(72) Inventors: **SHEN, Zeqing**; 3050 Bowers Avenue, Santa Clara, California 95054 (US). **QI, Bo**; 3050 Bowers Avenue, Santa Clara, California 95054 (US). **MALLICK, Abhijit Basu**; 3050 Bowers Avenue, Santa Clara, California 95054 (US).

(74) Agent: **SMIRK, Rebecca A.**; SERVILLA WHITNEY LLC, 33 Wood Avenue South, Suite 830, Iselin, New Jersey 08830 (US).

(81) Designated States (*unless otherwise indicated, for every kind of national protection available*): AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BN, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DJ, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IR, IS, IT, JO, JP, KE, KG, KH, KN, KP, KR, KW, KZ, LA, LC, LK, LR, LS, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PA, PE, PG, PH, PL, PT, QA, RO, RS, RU, RW, SA, SC, SD, SE, SG, SK, SL, ST, SV, SY, TH, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, WS, ZA, ZM, ZW.

(84) Designated States (*unless otherwise indicated, for every kind of regional protection available*): ARIPO (BW, GH, GM, KE, LR, LS, MW, MZ, NA, RW, SD, SL, ST, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, RU, TJ, TM), European (AL, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, RS, SE, SI, SK, SM, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, KM, ML, MR, NE, SN, TD, TG).

(54) Title: HDP SACRIFICIAL CARBON GAPFILL

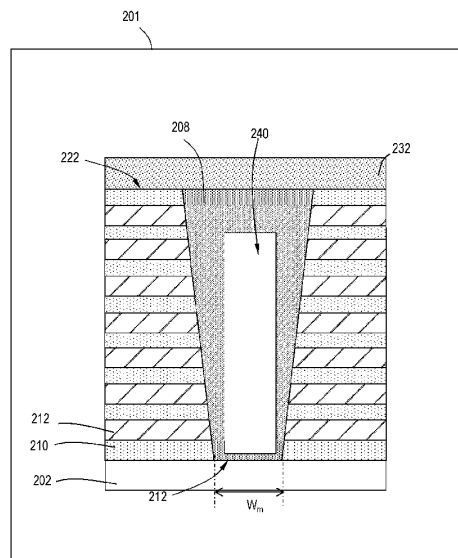


FIG. 2E

(57) Abstract: Methods for filling a substrate feature with a carbon gap fill, while leaving a void, are described. Methods comprise flowing a process gas into a high density plasma chemical vapor deposition (HDP-CVD) chamber, the chamber housing a substrate having at least one feature, the process gas comprising a hydrocarbon reactant, generating a plasma, and depositing a carbon film.

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Published:

— with international search report (Art. 21(3))